L Number	Hits	Search Text	DB	Time stamp
1	2482	(430/311).CCLS.	USPAT; US-PGPUB;	2003/11/23 15:10
			EPO; JPO; DERWENT	
2	344	((430/311).CCLS.) and ((hard or metal or	USPAT;	2003/11/23
		etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)	US-PGPUB; EPO; JPO;	15:17
3 .	106	(//420/244) CCI S) and // hand on model on	DERWENT	2003/11/23
	106	(((430/311).CCLS.) and ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or	USPAT; US-PGPUB;	15:17
		tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))	EPO; JPO; DERWENT	
	1473	(430/322).CCLS.	USPAT;	2003/11/23
			US-PGPUB;	15:17
			EPO; JPO;	
=	407	//420/222\ OCI E \ and // band as marked as	DERWENT	2002/44/22
5	197	((430/322).CCLS.) and ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or	USPAT; US-PGPUB;	2003/11/23 15:17
		tungsten or Ta or tantalum)	EPO; JPO;	15:17
		tangoton or ra or tantalanly	DERWENT	
6	77	(((430/322).CCLS.) and ((hard or metal or	USPAT;	2003/11/23
		etch\$3) adj (layer or film or mask)) and (W or	US-PGPUB;	15:18
		tungsten or Ta or tantalum)) and (Cr\$O\$N or	EPO; JPO;	į
•		(chrom\$4 with (oxide or oxy\$4) with nitr\$4))	DERWENT	
	1	09/683929	USPAT;	2003/11/22 16:52
			US-PGPUB; EPO; JPO;	10:52
			DERWENT	
-	6369	(430/5).CCLS.	USPAT;	2003/11/22
			US-PGPUB;	16:52
			EPO; JPO;	
	00454	(1) 1 (1) (1) (1)	DERWENT	2000/44/20
-	69151	((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or	USPAT;	2003/11/23 15:11
		tantalum)	US-PGPUB; EPO; JPO;	13.11
			DERWENT	
-	1078592	(Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4)	USPAT;	2003/11/23
		with nitr\$4))	US-PGPUB;	15:11
			EPO; JPO;	
	40404	/// hand an madel == -4-6-60 = 11 /1	DERWENT	2002/44/22
	18431	(((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or	USPAT; US-PGPUB;	2003/11/22 17:57
		tantalum)) and ((Cr\$O\$N or (chrom\$4 with	EPO; JPO;	17.57
		(oxide or oxy\$4) with nitr\$4)))	DERWENT	
-	7354	((((hard or metal or etch\$3) adj (layer or film	USPAT;	2003/11/22
		or mask)) and (W or tungsten or Ta or	US-PGPUB;	17:59
		tantalum)) and ((Cr\$O\$N or (chrom\$4 with	EPO; JPO;	
		(oxide or oxy\$4) with nitr\$4)))) and (mask or photomask or reticle) and (resist or photoresist)	DERWENT	

•	187	(((((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and ((Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)))) and (mask or photomask or reticle) and (resist or photoresist)) and ((430/5).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/22 18:07
•	6	"6472107"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/22 18:08
•	23616	(Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 08:47
-	246	430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 10:13
-	166	(430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 09:43
-	80	(430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))) not ((430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 09:43
•	73	((430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum)) and (charg\$4 or discharg\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 10:24